

UTILITIES TRANSFER SYSTEM IN A LITHOGRAPHY SYSTEM

ABSTRACT OF THE DISCLOSURE

Techniques for transferring utilities to and from a reticle or wafer stage in a
5 lithography system while minimizing physical disturbances that affect the stage are
described. These techniques involve transferring utilities to and from the stage without
making physical contact with the stage. Alternatively, utilities are transferred by making
physical contact with the stage while the stage is in a stationary position. In addition to
transferring utilities to and from the stage, devices such as processing devices, buffers
10 (storage mediums), electrical components, and mechanical components can be placed
within the stage to use and/or control the transferred utilities.